Recent Progress in Non-Cesiated III-Nitride Photocathodes

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Introduction

3x Directorate: Engineering and Science Division 38: Instruments and Science Data Systems Section 389: Instrument Electronics and Sensors

> Group 389E: Advanced Detector & Nanoscience Technologies Shouleh Nikzad (Supervisor) Doug Bell Jordana Blacksberg Frank Greer Blake Jacquot Todd Jones

The group works on advanced device concepts (mostly detector), including new materials.



Topics

- Motivation for III-N Photocathodes
- Delta-doping
- Progress in delta-doping for non-cesiated photocathodes
- AlGaN versus GaN
- Summary



Why III-Nitrides for Photocathodes?

- Low electron affinities in the Al_xGa_{1-x}N system.
- High chemical stability.
- Low inherent surface state charge.
- Tailorable UV response and solar blindness.
- Current UV photocathodes suffer from low QE and instability in the response





Photocathode Activation with Cesiation



•Quantum efficiency degrades rapidly under minute exposure to O_2 Degradation linked to oxidation of Cs.

•Cesiated AIGaN photocathodes are only appropriate for UHV environments.

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Approach

Goal: Demonstrate a non-cesiated III-N based photocathode

Cesiation alters surface band structure using low-work function metal Our approach is based on experience with other devices and materials*

- Piezoelectrically Enhanced Photocathode (PEPC)
- Delta doped Enhanced Photocathode (DDEPC)
- Take advantage of lower work function of AlGaN

*Hoenk, et al., Nikzad et al., Blacksberg, et al., Delta doped CCDs



Delta-doped Photocathode





Schematic of Emission Measurement





IPE Spectrum for GaN / δ-Si / p-GaN





Effect of Delta-layer Cap Thickness on Emission Intensity



Thinner GaN cap layers produce an increase in emission intensity, due to decreased hot-electron scattering.



Effect of Delta-layer Cap Thickness on Emission Intensity



Very short attenuation length for the cap layer indicates strong scattering. Improvement in cap quality is essential.



Effect of Delta-layer Cap Thickness on Emission Threshold



Only a weak dependence of emission threshold on GaN cap layer thickness observed.



Effect of Si Delta-doping Density on Emission Threshold



Bare GaN has a high emission threshold. Si delta-doping produces a rapid reduction of threshold until the conduction band edge reaches the Fermi level.



Effect of Delta Layer Doping Density on Emission Intensity





Effect of Bulk p-Doping on Emission Intensity



Increased p-doping of the bulk GaN reduces the width of the surface well, thus decreasing scattering losses during well traversal.



IPE Spectrum for AlGaN / δ-Si / p-GaN







Summary

III-N photocathode activation is investigated without use of cesiation

These techniques offer the advantage of stable response even with exposure to air

GaN samples grown on sapphire were examined as delta doped enhanced photocathodes

Effect of cap layer, dopant density in the bulk, and dopant density in the delta layer were determined and optimized

Work is underway to integrate other effects to achieve true NEA without cesiation